

# Supporting Information

## **Novel multi-functional sites in boron-based bi-atom catalysts synergistically boost C-C coupling for efficient CO electroreduction towards ethanol**

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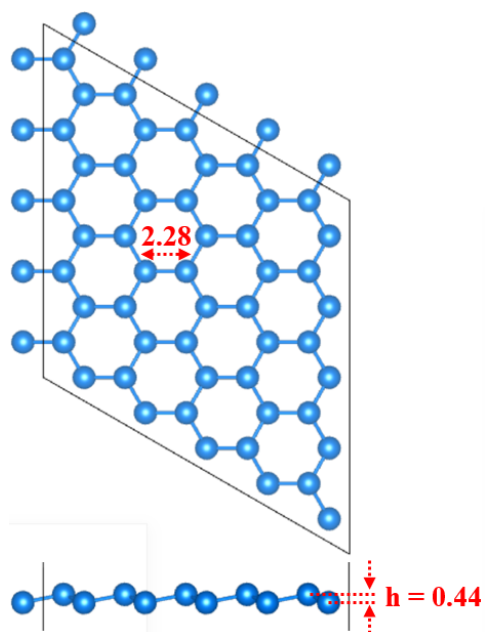
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## Computational Methods

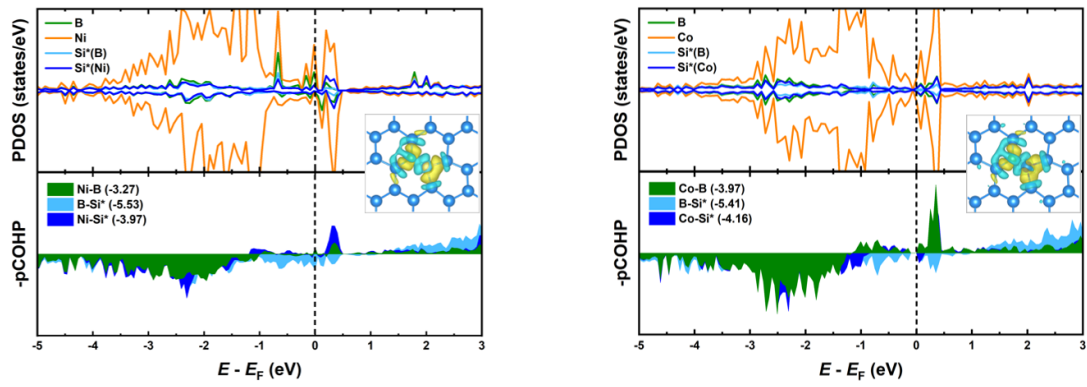
The computational hydrogen electrode model (CHE)<sup>1</sup> was employed to calculate Gibbs free energy ( $\Delta G$ ) change of each elementary reactions via  $\Delta G = \Delta E + \Delta E_{\text{ZPE}} - T\Delta S + \Delta G_{\text{U}} + \Delta G_{\text{pH}}$  where  $\Delta E$ ,  $\Delta E_{\text{ZPE}}$ , and  $\Delta S$  denote the electronic energy difference, the zero-point energy change and the entropy change. Zero-point energy was obtained from the vibrational frequencies via the equation:  $E_{\text{ZPE}} = \sum_i \hbar \nu_i / 2$ , and entropy was calculated using the following equation:  $S = k_B T \sum_i^{3N} \left[ -\ln \left( 1 - e^{-\frac{\varepsilon_i}{k_B T}} \right) + \frac{\varepsilon_i}{k_B T \left( 1 - e^{-\frac{\varepsilon_i}{k_B T}} \right)} \right]$  where  $\varepsilon_i$  is the vibrational energy of mode  $i$ ,  $N$  is the number of atoms in the adsorbates,  $k_B$  is Boltzmann constant ( $1.38 \times 10^{-23} \text{ JK}^{-1}$ ),  $T = 298.15 \text{ K}$ .  $\Delta G_{\text{U}}$  is the free energy contribution related to electrode potential  $U$ , as expressed via  $\Delta G_{\text{U}} = -eU$  ( $e$  and  $U$  are the number of transferred electrons and applied electrode potential, respectively).  $\Delta G_{\text{pH}}$  is the free energy correction of pH,  $\Delta G_{\text{pH}} = 0$  for acidic medium in this work. The entropies of free gas molecules were taken from the National Institute of Standards and Technology (NIST) database. The limiting potential ( $U_{\text{L}}$ ) of the reaction was calculated as  $U_{\text{L}} = -\Delta G_{\text{max}}/e$ , where  $\Delta G_{\text{max}}$  is the free energy change of potential determining step and  $e$  is the corresponding number of electrons transferred. Average adsorption energy of CO\* co-adsorbed species is calculated as  $\text{avg}_{\text{ads}}[2\text{CO}^*] = (E_{2\text{CO}^*\text{-BACs}} - E_{\text{BACs}} - 2^*E_{\text{CO}(\text{gas})})/2$ , where  $E_{2\text{CO}^*\text{-BACs}}$ ,  $E_{\text{BACs}}$  and  $^*E_{\text{CO}(\text{gas})}$  are total energies of 2CO\*-adsorbed BACs, bare BACs and CO gas phase.

The formation energy of B-X bi-dopants into silicene (B-X@Si) is calculated as:  $E_f = E_{\text{BACs}} - E_{\text{DV-Si}} - E_{\text{B dopant}(\text{bulk})} - E_{\text{X dopant}(\text{bulk})}$ , where  $E_{\text{BACs}}$ ,  $E_{\text{DV-Si}}$ ,  $E_{\text{B dopant}(\text{bulk})}$  and  $E_{\text{X dopant}(\text{bulk})}$  are the total energies of BACs, di-vacancy (DV) silicene, and single B and transition metal (TM) dopant in bulk state. The electrochemical stability of transition metals in B-doped silicene (B@Si) can be evaluated by the dissolution potential ( $U_{\text{diss}}$ ),<sup>2</sup> which is defined

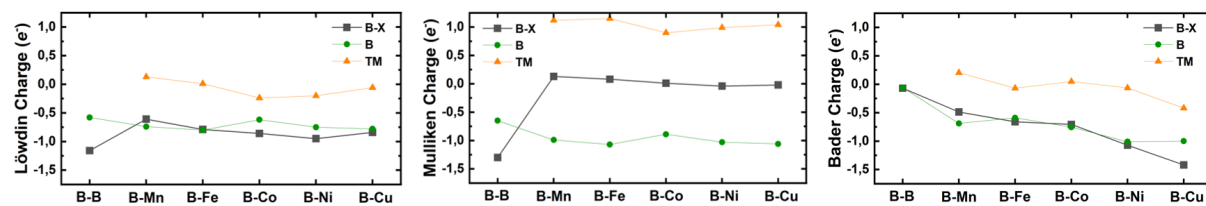
as  $U_{diss} = U_{diss}^o - E_f/Ne$ , where  $U_{diss}^o$ ,  $E_f$  and  $N$  are the standard dissolution potential of pure bulk, formation energy ( $E_f = E_{BACS} - E_{SV-B@Si} - E_{TM\ dopant(bulk)}$ ;  $E_{BACS}$ ,  $E_{SV-B@Si}$  and  $E_{TM\ dopant(bulk)}$  are the total energies of BACs, single vacancy (SV) B@Si, and single transition metal dopant in bulk state, respectively), and the number of electrons involved in the dissolution. Hereby, materials with  $U_{diss} > 0$  V are considered electrochemically stable.



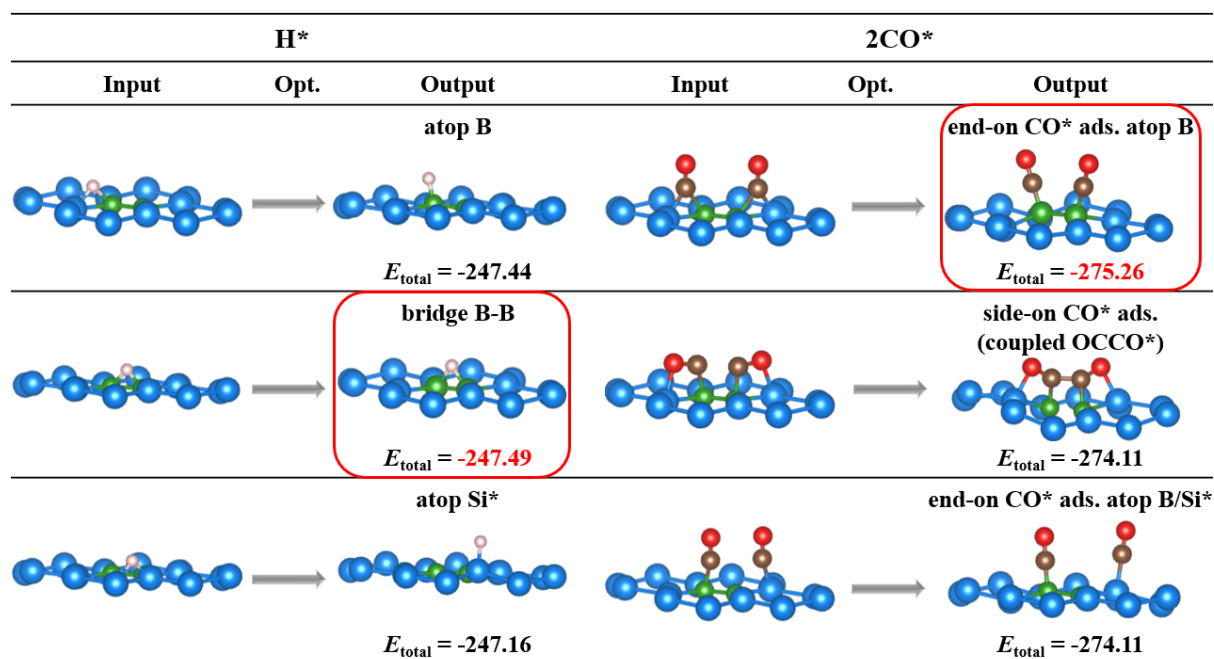
**Fig. S1** Schematic representation of pristine Silicene (Si) from both top and side views, together with nearest neighbour distance and buckling height ( $h$ ). Unit: Å. Color code: Si – light blue.



**Fig. S2.** Partial density of states (PDOS) of dopants (B/Ni/Co) and one their nearest neighboring host atom (Si\*); projected crystal orbital Hamilton population (pCOHP) of the dopant-dopant and dopant-host atom bonds within heterogeneous B-Ni@Si and B-Co@Si structures. The Fermi level displayed in dashed line is set to zero. Their corresponding charge density difference are also displayed. The isosurface value is set to  $0.0025 \text{ e}/\text{\AA}^3$ , and the yellow (cyan) regions represent charge accumulation (depletion).

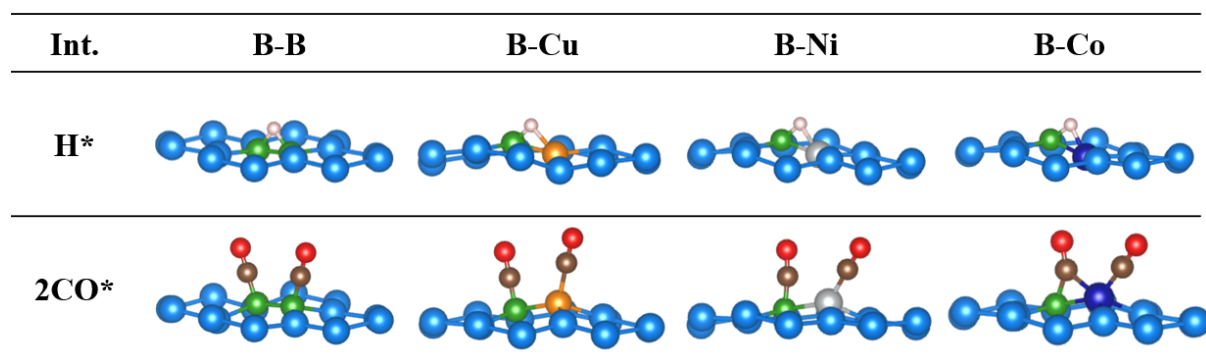


**Fig. S3.** Löwdin, Mulliken and Bader charge variations of B, transition metals (TM) and total B-X (X: B or TM) pairs within the pure B-X systems.



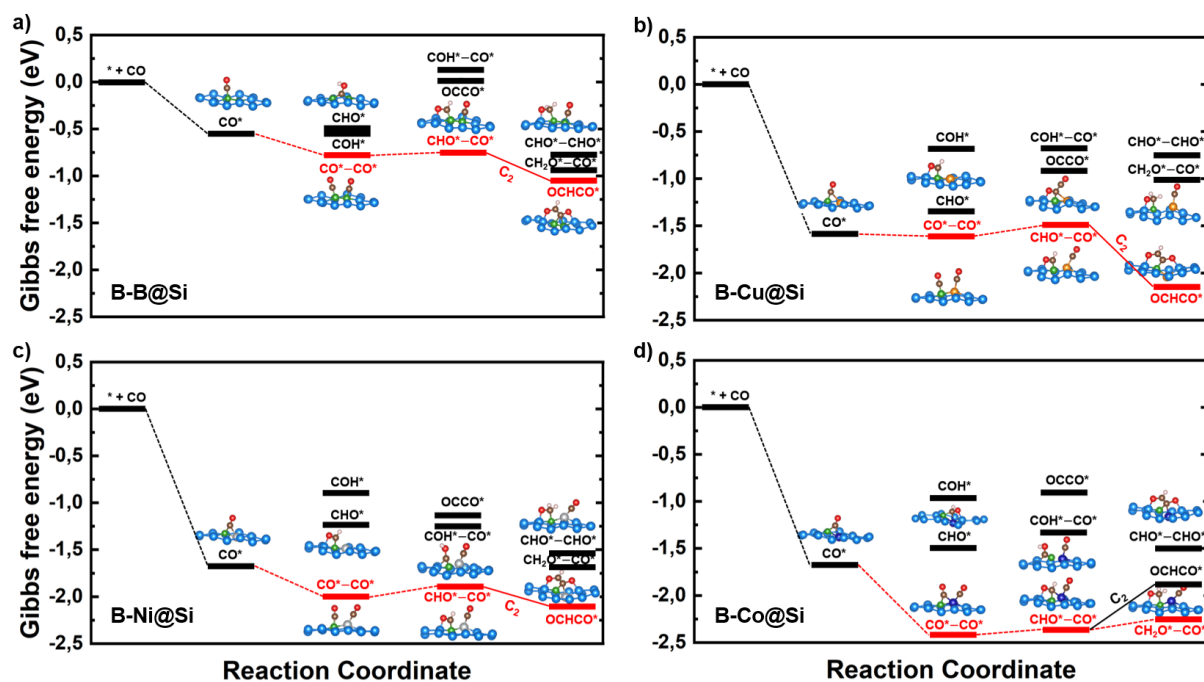
**Fig. S4** All possible scenarios of H and 2CO adsorbed on B-B@Si before and after optimization (opt.) with their corresponding total energy ( $E_{\text{total}}$ ). Units: eV. Lowest-energy optimized configurations for the H\* and 2CO\* intermediates are highlighted in red. Color code: B – green, Si – light blue, H – light pink, C – brown and O – red.

For H\* intermediate, regardless of the initial guess of H adsorption sites (atop B, or bridge B-Si\*, or Si\*-Si\*sites, H preferentially adsorbs on the bridge site of two dopants (B-B), forming the most stable H\* configuration post-optimization. Likewise, for the 2CO\* intermediate, the lowest-energy configuration is obtained as two CO molecules vertically adsorb onto two dopant active sites.



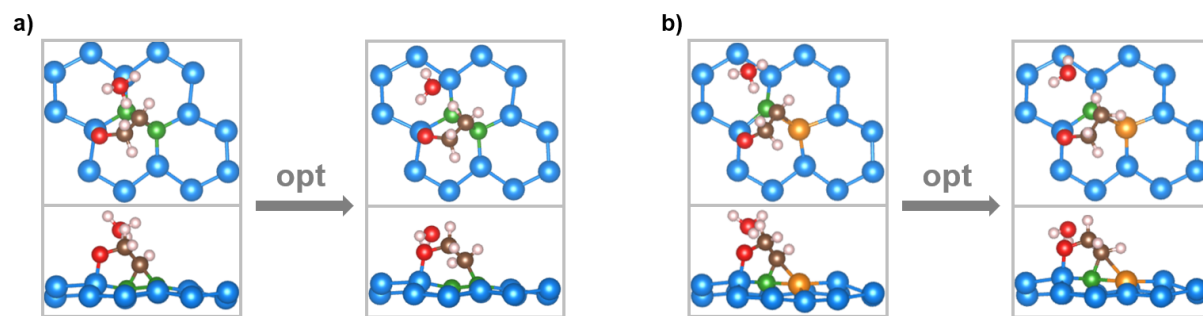
**Fig. S5.** Corresponding lowest-energy configurations of H\* and 2CO\* adsorption on B-B@Si, B-Cu@Si, B-Ni@Si and B-Co@Si. Color code: B – green, Co – blue, Ni – silver, Cu – orange, Si – light blue, H – light pink, C – brown and O – red.



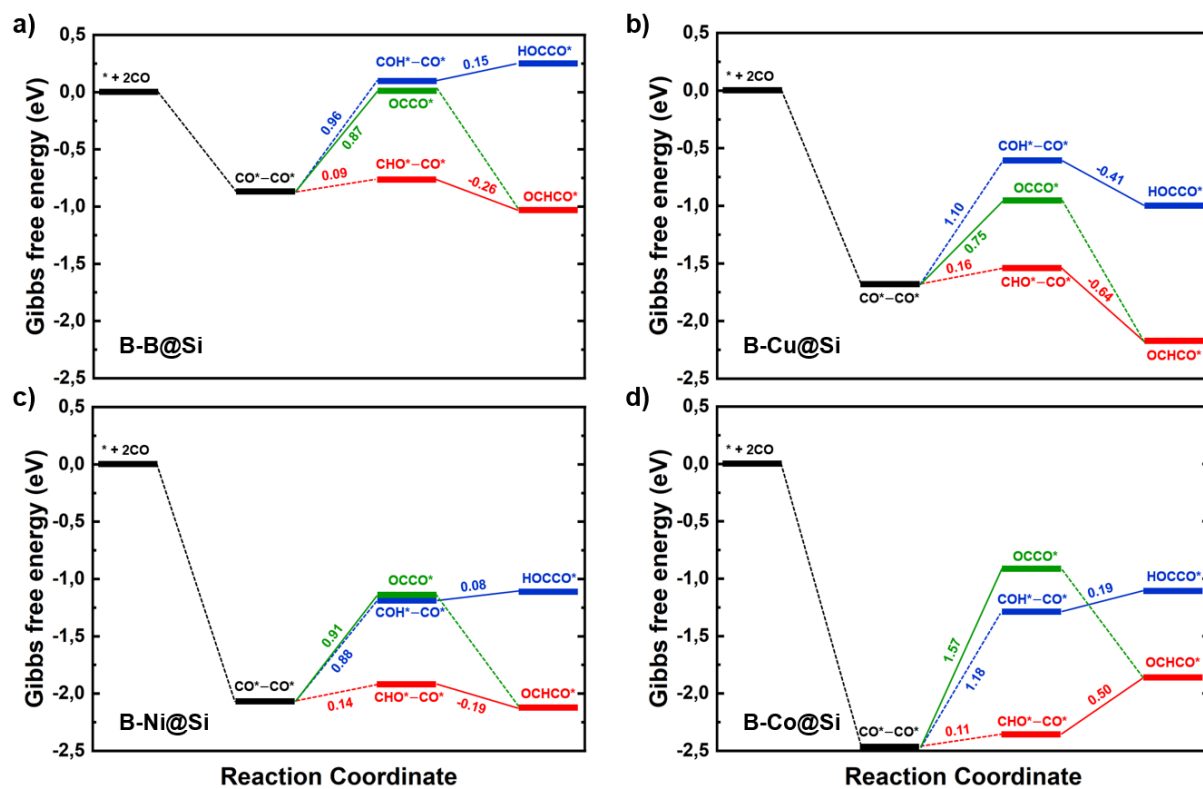


**Fig. S6.** Free energy profiles possible  $C_1$  and  $C_2$  pathways during the initial stage of CORR process, starting from one CO molecule adsorption on a) B-B@Si, b) B-Cu@Si, c) B-Ni@Si and d) B-Co@Si at 0 V (*vs* RHE). Inserts display the corresponding optimized structures of reaction intermediates. The solid lines indicate the C–C coupling step. The red lines represent the most thermodynamically favorable route. Color code: B – green, Cu – orange, Ni – silver, Co – dark blue, Si – light blue, C – brown, O – red and H – light pink.

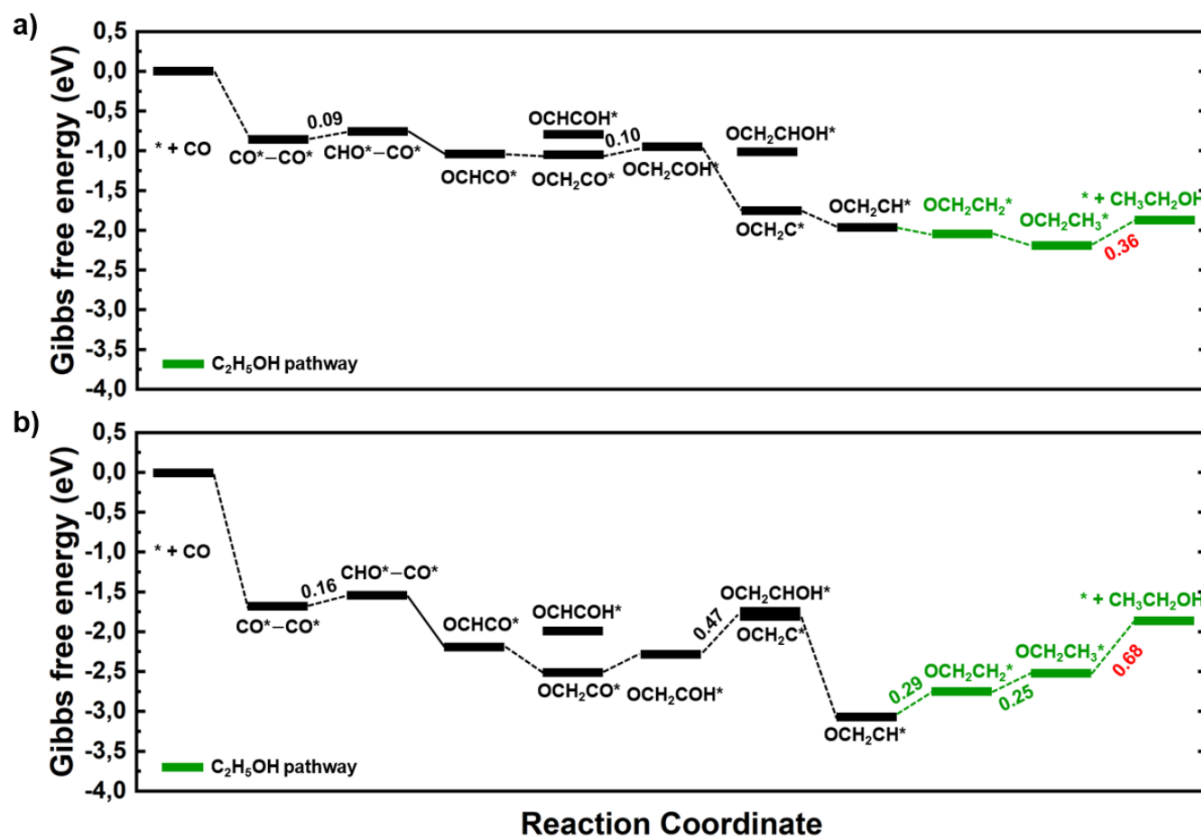
Four structures are more energetically inclined to adsorb an additional CO molecule, forming a decoupled  $\text{CO}^*-\text{CO}^*$  intermediate (comprising two separate  $C_1$  fragments, particularly  $2\text{CO}^*$ ) rather than proceeding with protonation to generate  $C_1$  intermediates ( $\text{CHO}^*$  or  $\text{COH}^*$ ). The decoupled  $\text{CO}-\text{CO}^*$  intermediate is then more favorably hydrogenated to form decoupled  $\text{CHO}-\text{CO}^*$ . The subsequent preferential coupling step of two  $C_1$  fragments ( $\text{CHO}^*$  and  $\text{CO}^*$ ) within the decoupled  $\text{CHO}-\text{CO}^*$  to form a coupled  $\text{OCHCO}^*$  intermediate occurs on three BACs (B-B@Si, B-Cu@Si and B-Ni@Si), rather than its competitive protonation steps to form decoupled  $\text{CH}_2\text{O}^*-\text{CO}^*$  (or  $\text{CHO}^*-\text{CHO}^*$ ).



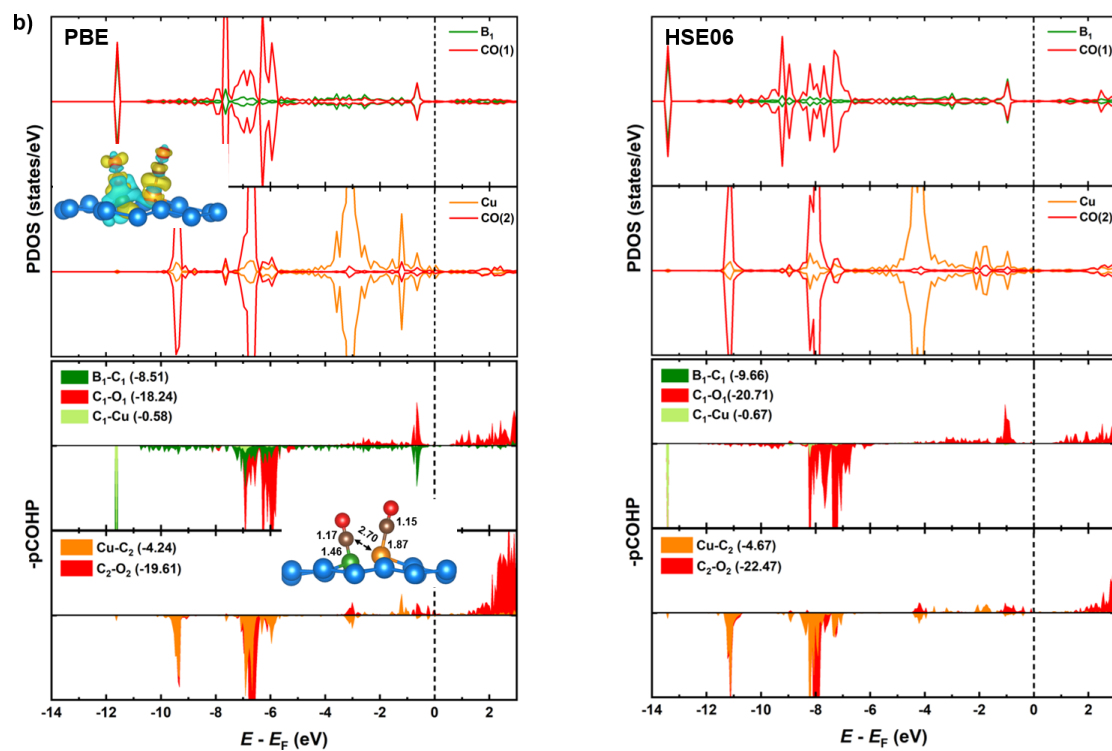
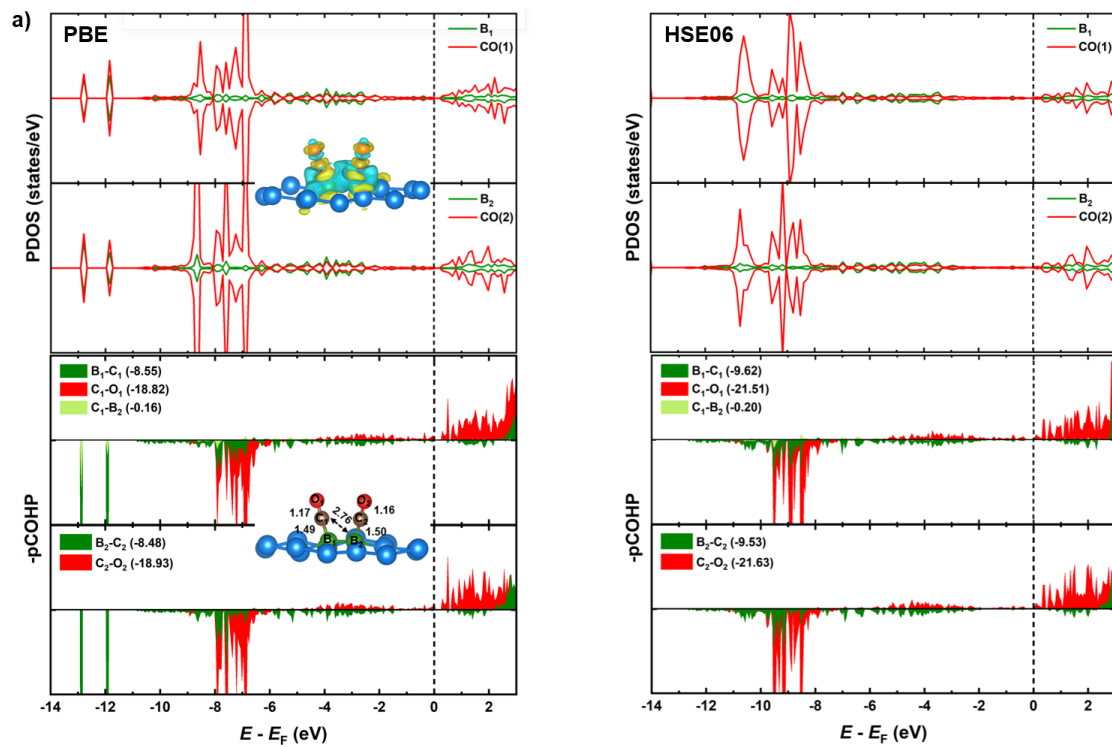
**Fig. S7.** Top and side views of OCH<sub>2</sub>CH\* adsorption on (a) B-B@Si and (b) B-Cu@Si with the presence of H<sub>3</sub>O<sup>+</sup> before and after structure optimization. Starting geometries with H<sub>3</sub>O<sup>+</sup> placed in the vicinity of OCH<sub>2</sub>CH\*.

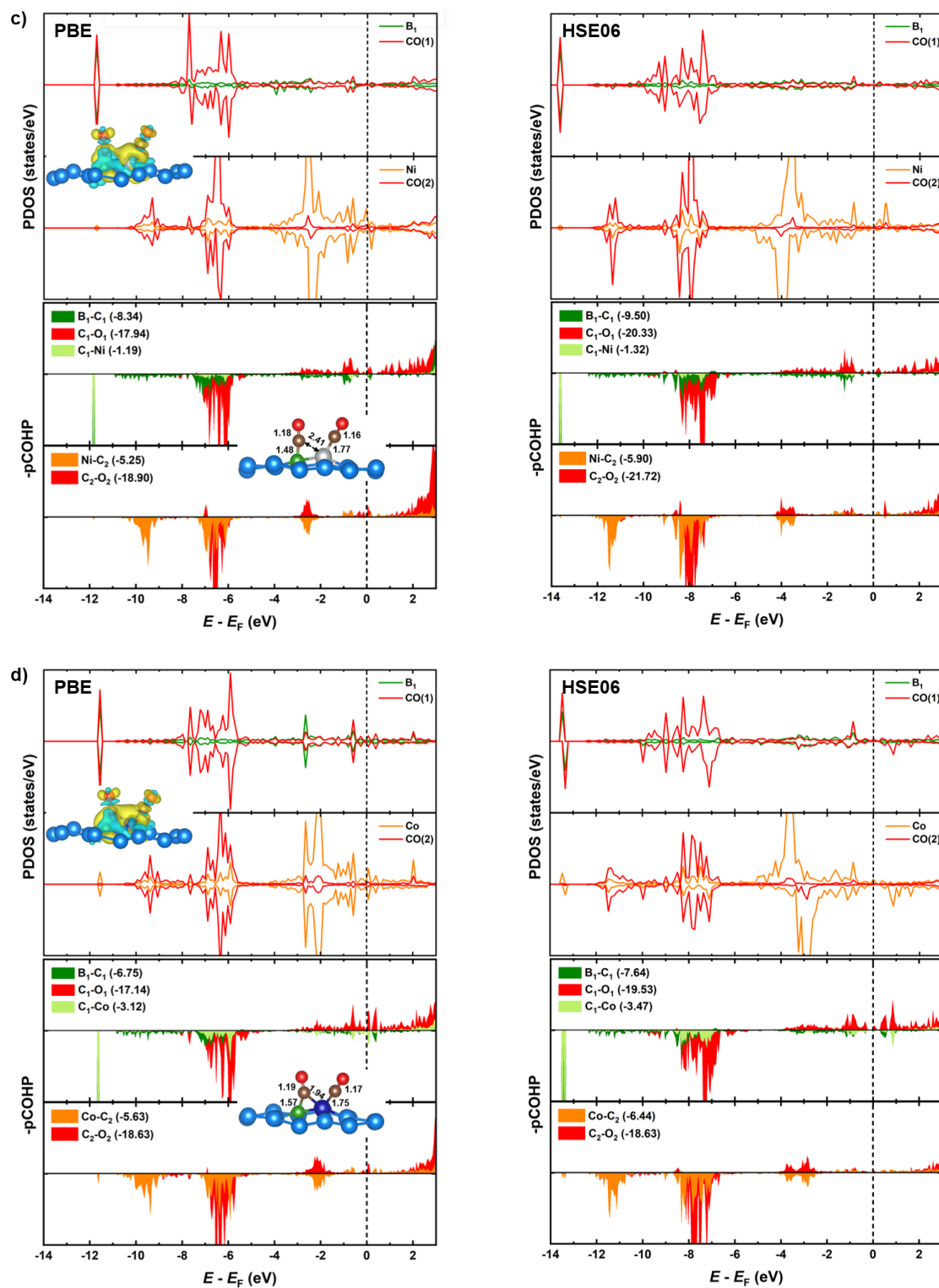


**Fig. S8.** Free energy profiles of different C-C coupling paths in vacuum on **a)** B-B@Si, **b)** B-Cu@Si, **c)** B-Ni@Si and **d)** B-Co@Si at 0 V (vs RHE). The solid lines indicate the C-C coupling step.



**Fig. S9** Free-energy profiles for CO reduction in vacuum on **a)** B-B@Si and **b)** B-Cu@Si. The potential determining step is labeled with the corresponding free energy change in red color. The green line demonstrates the best overall pathways towards CH<sub>3</sub>CH<sub>2</sub>OH. The solid lines indicate the C-C coupling step.





**Fig. S10.** Partial density of states (PDOS) of dopants and two adsorbed CO\* species (upper panels) obtained by PBE and HSE06 functionals on (a) B-B@Si, (b) B-Cu@Si, (c) B-Ni@Si and (d) B-Co@Si. Their corresponding charge density difference are also displayed. The isosurface value is set to 0.0025  $e/\text{\AA}^3$ , and the yellow (cyan) regions represent charge accumulation (depletion). Projected crystal orbital Hamiltonian population (pCOHP) of the 2CO\* intermediate. The Fermi level displayed in dashed line is set to zero. Their geometries with bond lengths are also displayed.

<b>Systems</b>	<b><math>d_{B-X}</math> (Å)</b>	<b><math>d_{B-Si^*}</math> (Å)</b>	<b><math>d_{TM-Si^*}</math> (Å)</b>
<b>B-B@Si</b>	1.70	2.01	
<b>B-Co@Si</b>	1.91	1.97	2.22
<b>B-Ni@Si</b>	1.96	1.94	2.20
<b>B-Cu@Si</b>	2.02	1.94	2.31

**Table S1** Bond lengths of two dopants ( $d_{B-X}$ ), dopant and its host neighbor ( $Si^*$ ) in B-X@Si. Units: Å

Adsorbed species	IpCOHP (bonds)	Functionals	B-B@Si	B-Cu@Si	B-Ni@Si	B-Co@Si
CO(1)*	C <sub>1</sub> -B	PBE	-8.55	-8.51	-8.34	-6.75
		HSE06	-9.62	-9.66	-9.50	-7.64
	C <sub>1</sub> -O <sub>1</sub>	PBE	-18.82	-18.24	-17.94	-17.14
		HSE06	-21.51	-20.71	-20.33	-19.53
	C <sub>1</sub> -B <sub>2</sub> (TM)	PBE	-0.16	-0.58	-1.19	-3.12
		HSE06	-0.20	-0.67	-1.32	-3.47
CO(2)*	B <sub>2</sub> (TM)-C <sub>2</sub>	PBE	-8.48	-4.24	-5.25	-5.63
		HSE06	-9.53	-4.67	-5.90	-6.44
	C <sub>2</sub> -O <sub>2</sub>	PBE	-18.93	-19.61	-18.90	-18.63
		HSE06	-21.63	-22.47	-21.72	-21.28

**Table S2** IpCOHP values of key bonds in CO(1)-CO(2)\*-adsorbed B-X@Si intermediates taken from Fig. S10.



Structures	Active sites	Functionals	$\mu_{\text{CHO-CO}^*}$	$\mu_{\text{OCHCO}^*}$	$\Delta\mu$ ( $\mu_{\text{B}}$ )
<b>B-B@Si</b>	<b>B<sub>1</sub></b>	PBE	0.01	0.00	
		HSE06	0.00	0.00	
	<b>B<sub>2</sub></b>	PBE	0.00	0.00	
		HSE06	0.00	0.00	
	<b>Total (B<sub>1</sub>-B<sub>2</sub>)</b>	<b>PBE</b>	<b>0.01</b>	<b>0.00</b>	<b>-0.01</b>
		<b>HSE06</b>	<b>0.00</b>	<b>0.00</b>	<b>0.00</b>
<b>B-Cu@Si</b>	<b>B</b>	PBE	0.00	0.00	
		HSE06	0.00	0.00	
	<b>Cu</b>	PBE	0.00	0.00	
		HSE06	0.00	0.00	
	<b>Total (B-Cu)</b>	<b>PBE</b>	<b>0.00</b>	<b>0.00</b>	<b>0.00</b>
		<b>HSE06</b>	<b>0.00</b>	<b>0.00</b>	<b>0.00</b>
<b>B-Ni@Si</b>	<b>B</b>	PBE	0.00	0.03	
	<b>Ni</b>	PBE	0.00	0.18	
	<b>Total</b>	<b>PBE</b>	<b>0.00</b>	<b>0.21</b>	<b>0.21</b>
<b>B-Co@Si</b>	<b>B</b>	PBE	0.00	-0.02	
	<b>Co</b>	PBE	0.00	0.45	
	<b>Total</b>	<b>PBE</b>	<b>0.00</b>	<b>0.43</b>	<b>0.43</b>

**Table S3** Magnetic moments calculated by PBE and HSE06 functionals in two key intermediates CHO-CO\* and OCHCO\* intermediates across four systems. Units:  $\mu_{\text{B}}$

There is no magnetic moments at the two B active sites in the two CHO-CO\*/OCHCO\*-adsorbed homo-B-B@Si intermediates, resulting in  $\Delta\mu \approx 0\mu_{\text{B}}$ . Moreover, the incorporation of Cu in hetero-B-Cu@Si for the two intermediates does not alter their electronic states, also leading to  $\Delta\mu = 0\mu_{\text{B}}$ . These values, computed using the PBE functional, for the two most promising catalysts, B-B@Si and B-Cu@Si, are also compared with hybrid calculations using the HSE06 functional. Meanwhile, the other two hetero-B-Ni/Co@Si experience a slight change in  $\Delta\mu$  ( $0.21/0.43\mu_{\text{B}}$ ), primarily due to the marginally higher spin state of the TM (Ni/Co) in the coupled-OCHCO\* intermediate. The importance of spin state is also reflected in the difference in spin-up and spin-down PDOS as shown in Fig. 9.

- 1 J. K. Nørskov, J. Rossmeisl, A. Logadottir, L. Lindqvist, J. R. Kitchin, T. Bligaard and H. Jónsson, *J. Phys. Chem. B*, 2004, **108**, 17886–17892.
- 2 J. Greeley and J. K. Nørskov, *Electrochimica Acta*, 2007, **52**, 5829–5836.